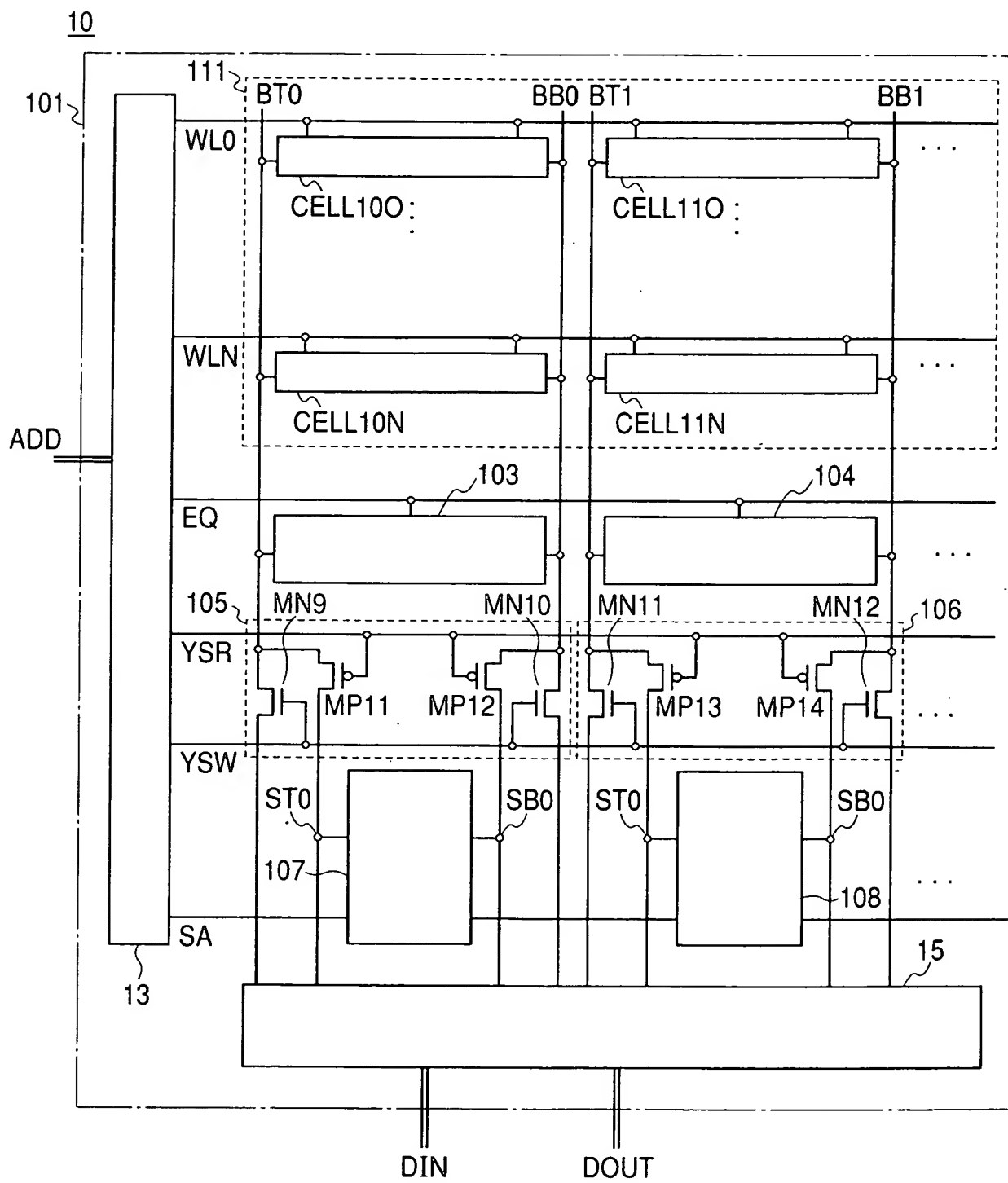
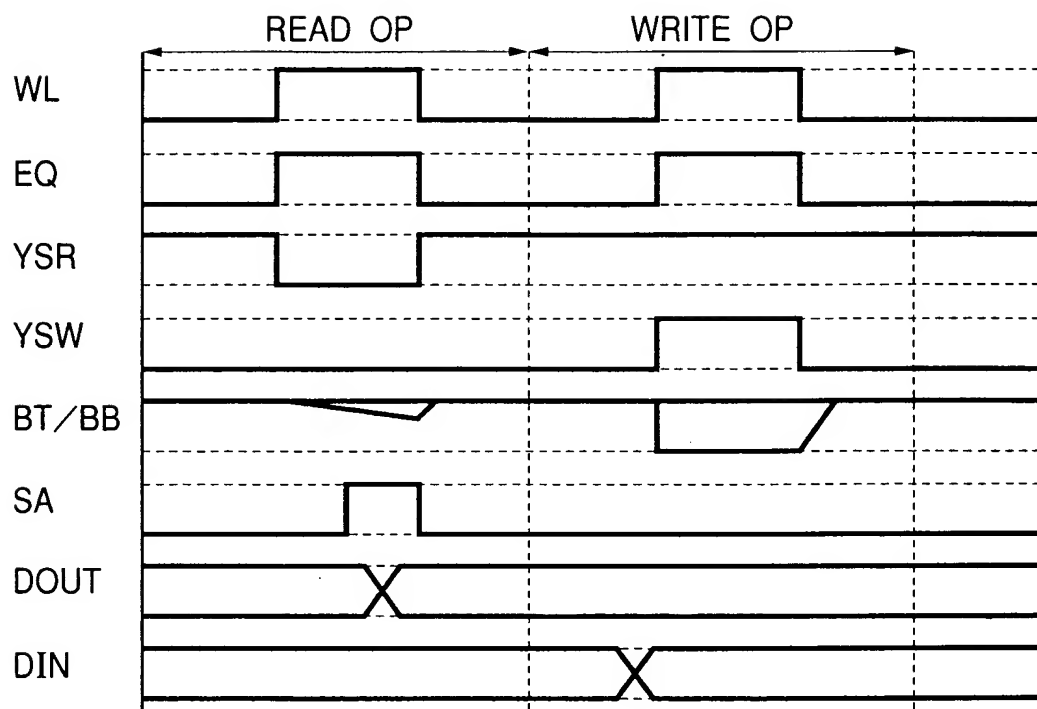
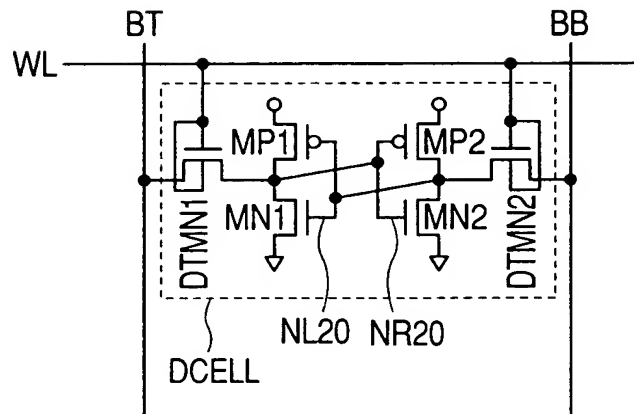


FIG. 1



*FIG. 2*

**FIG. 3**



**FIG. 4**

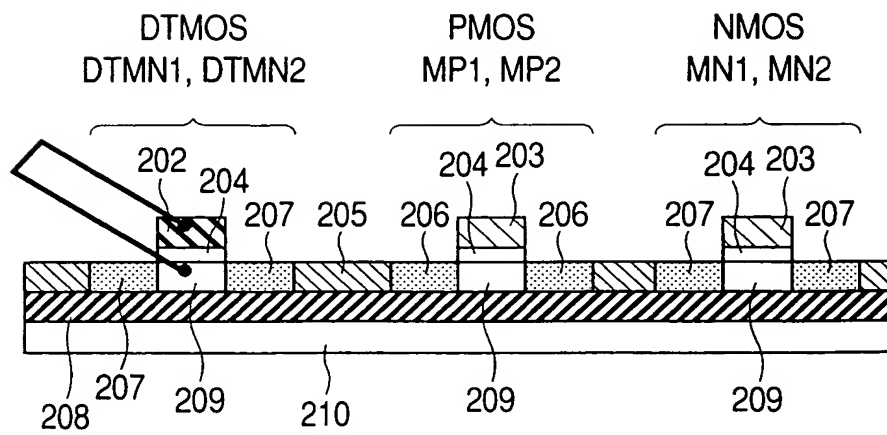


FIG. 5

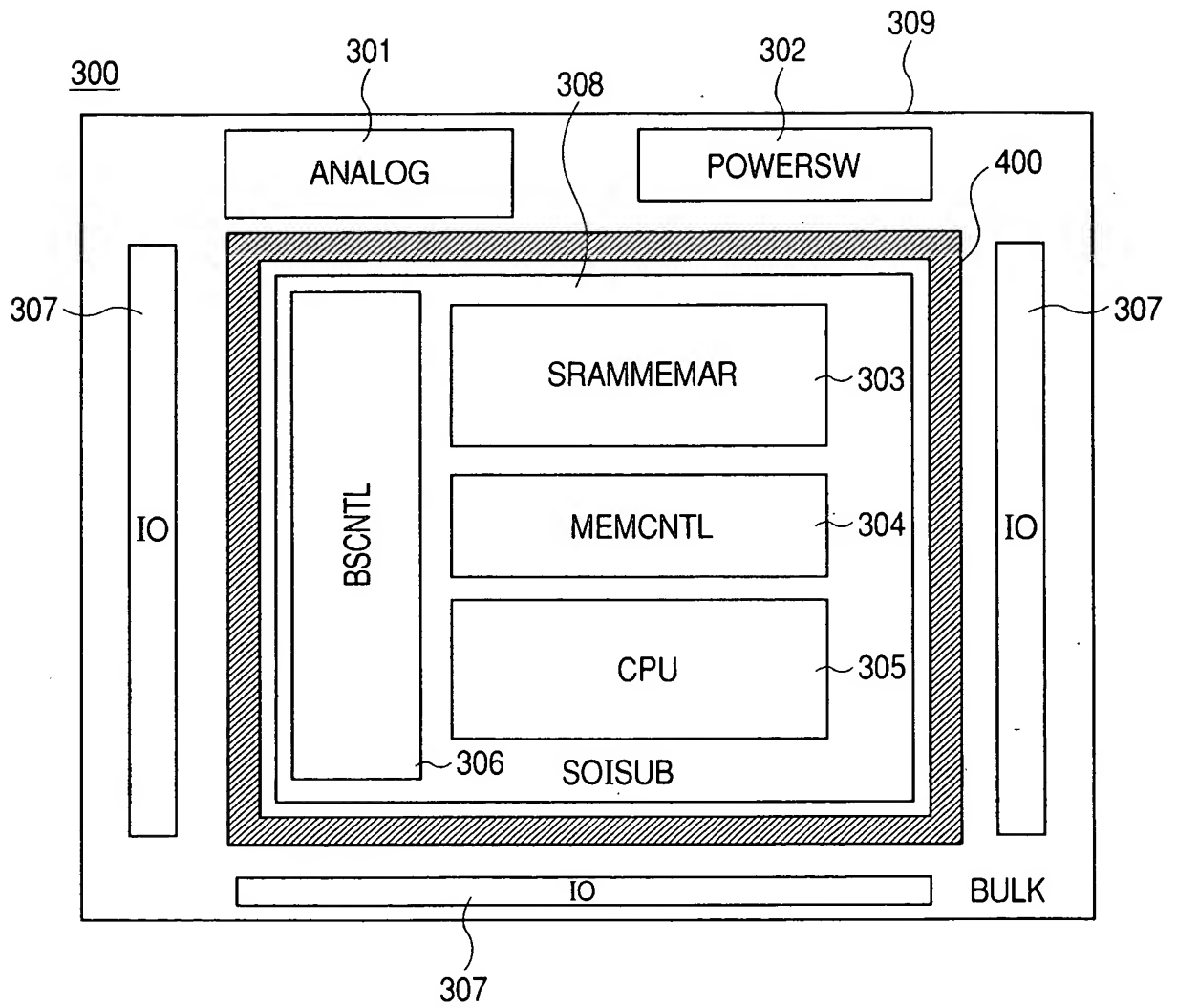


FIG. 6

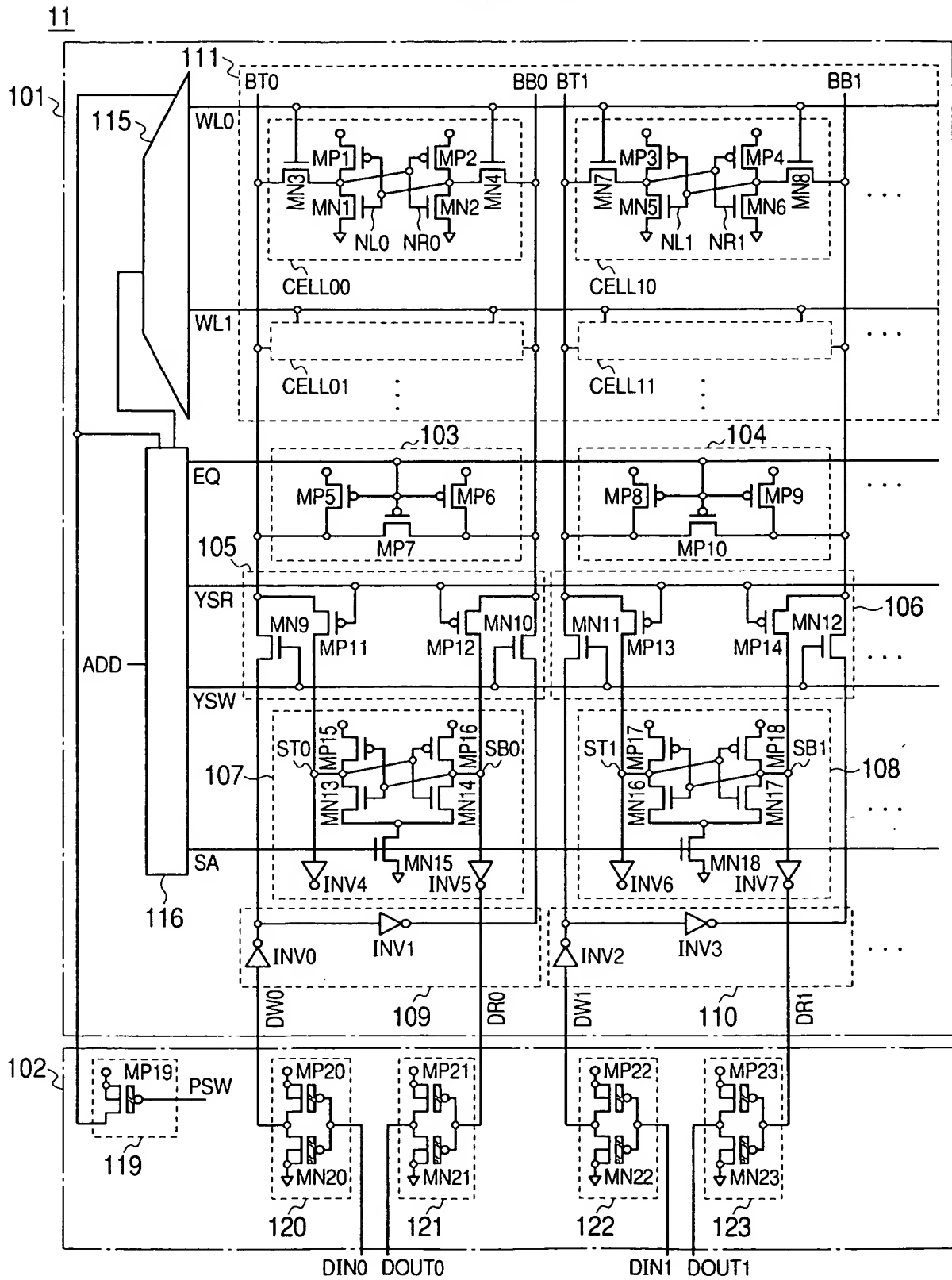


FIG. 7

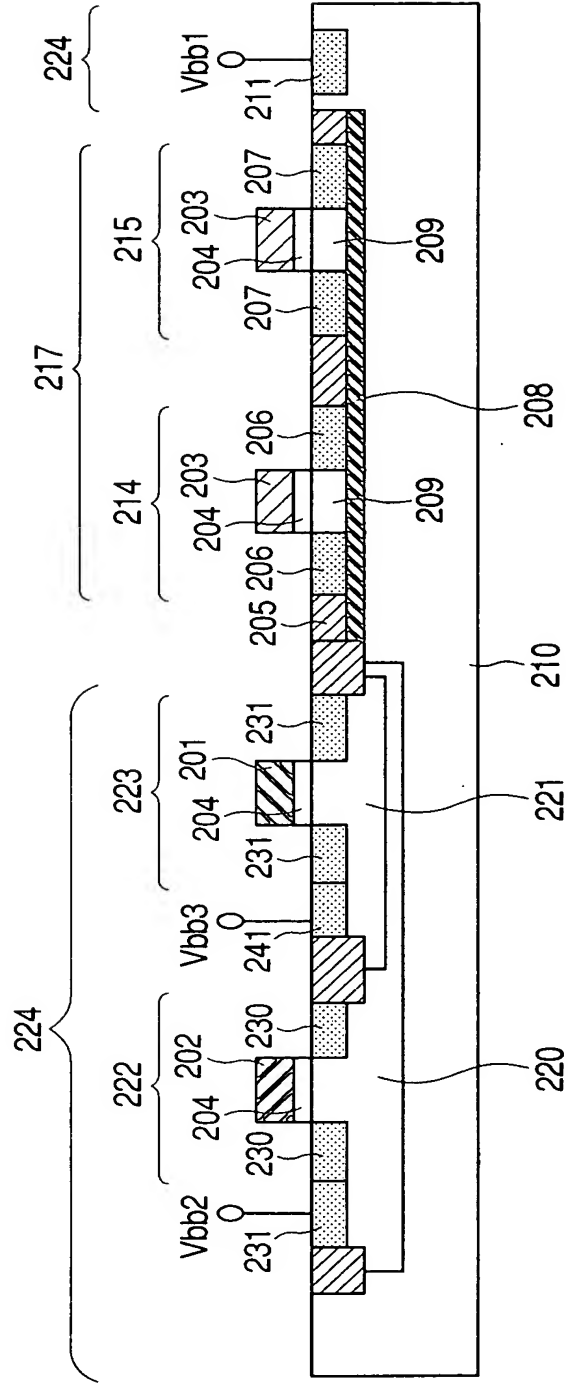


FIG. 8

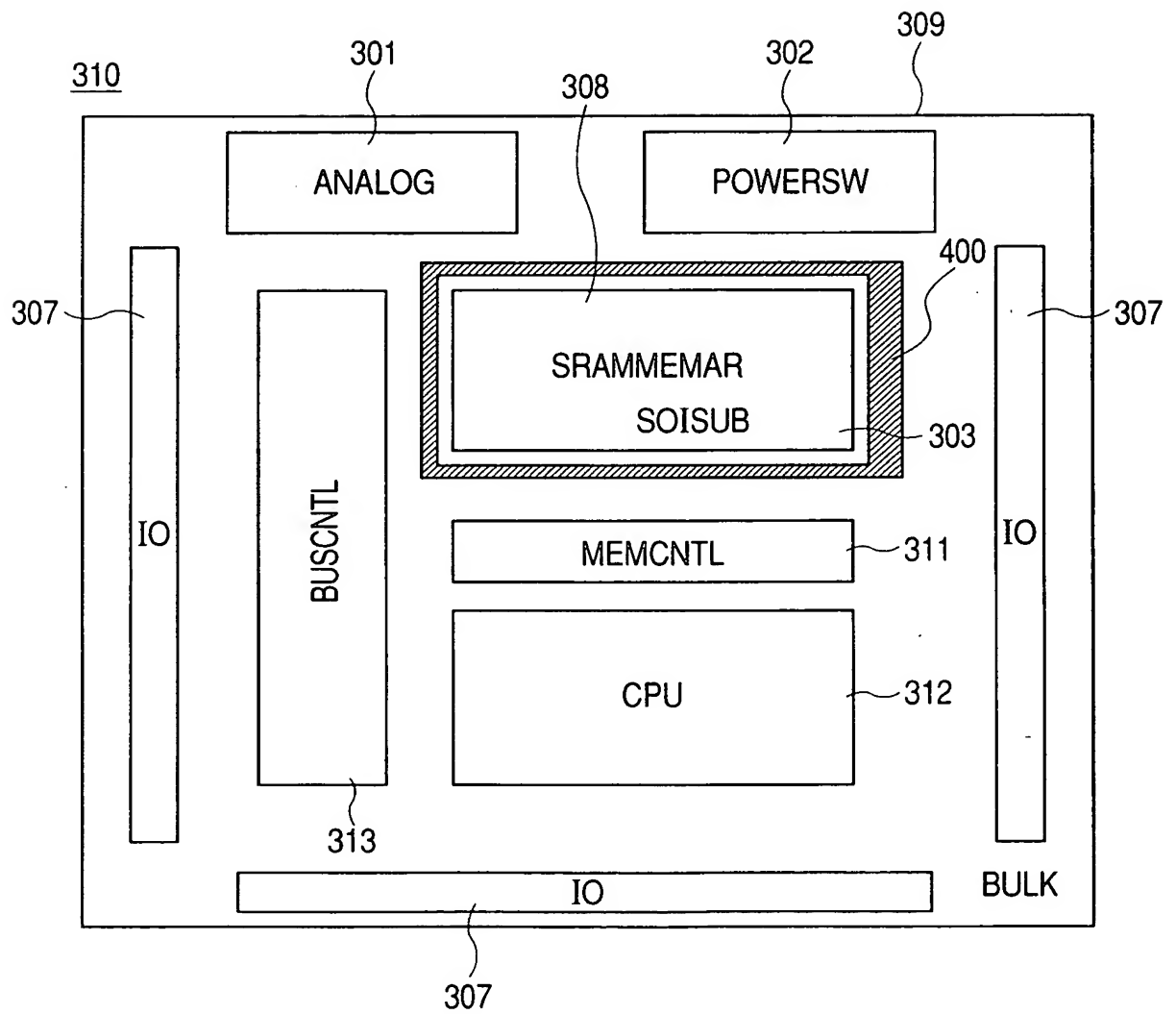


FIG. 9

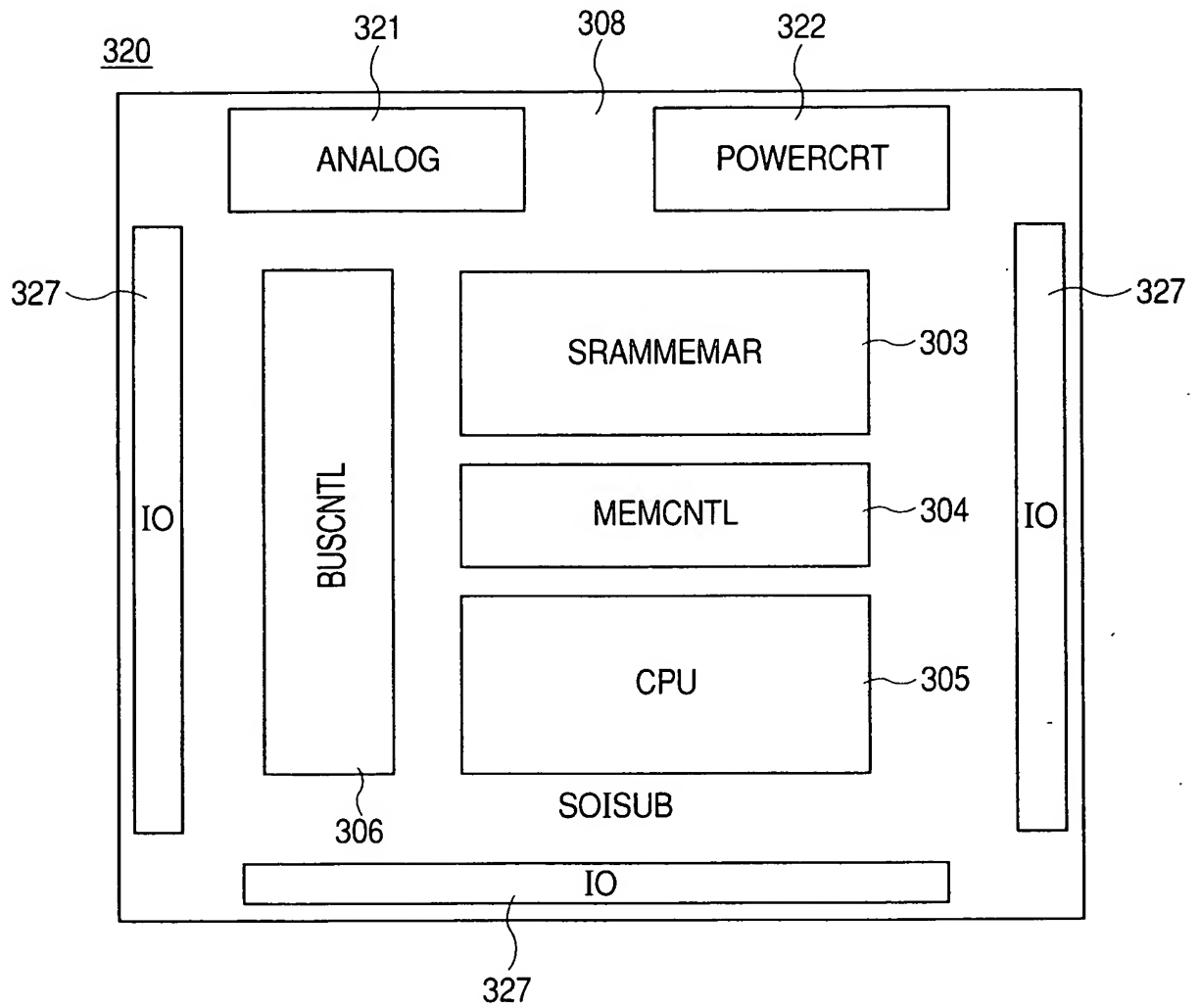




FIG. 10

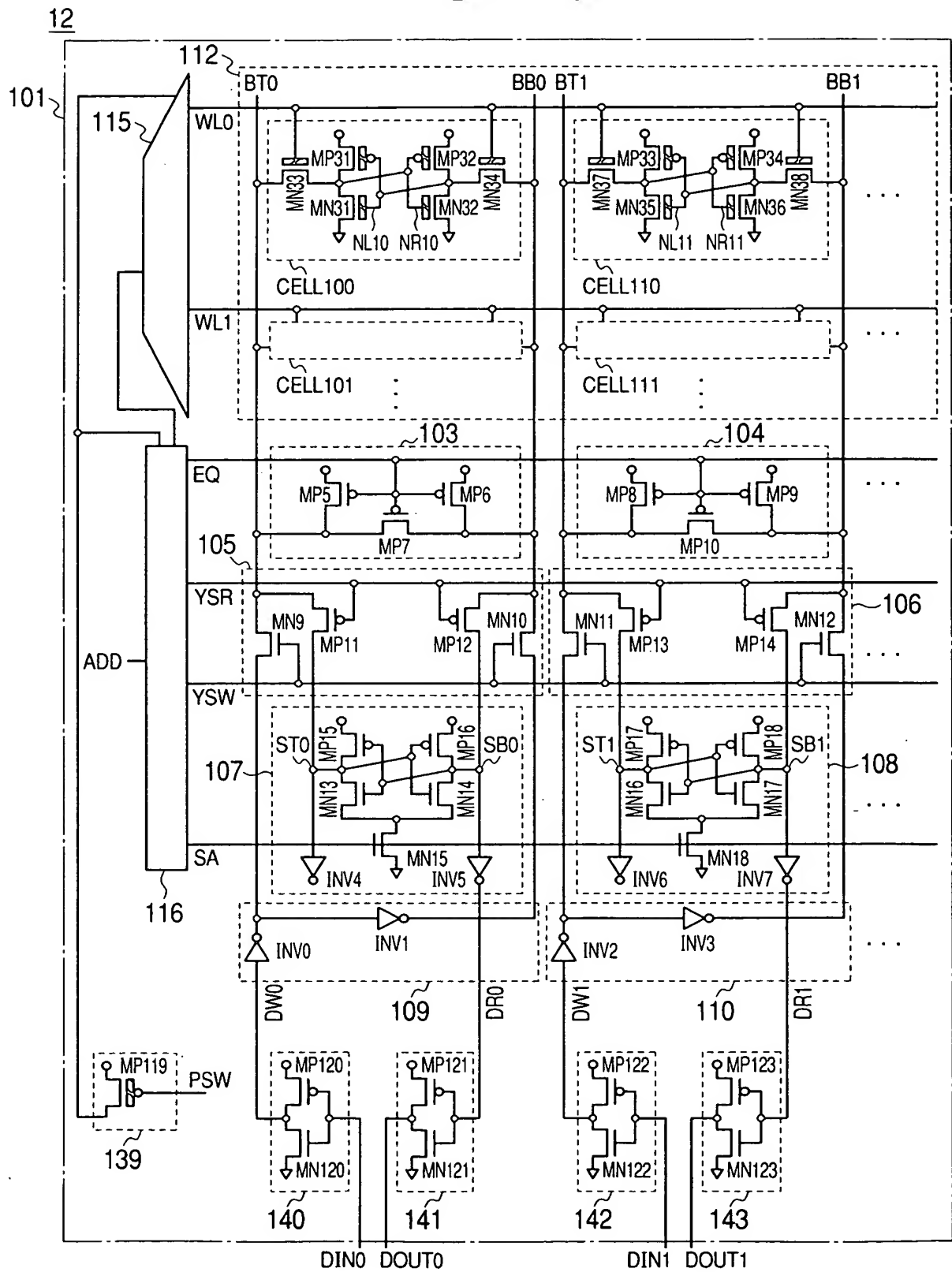


FIG. 11

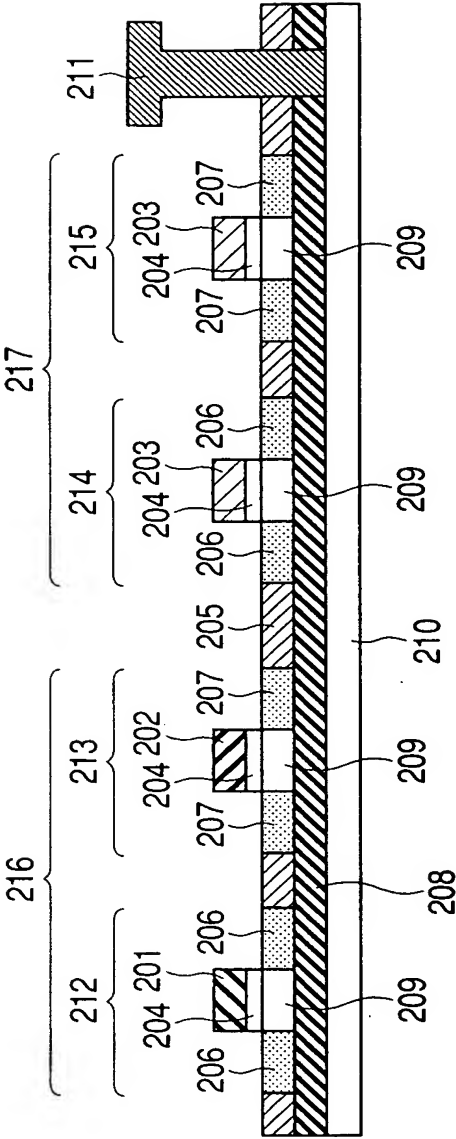


FIG. 12

SOISUB		HIGHSPEED					STANDARD				
		SUB	GATEMAT	GATEIMP	SOIVBB	VT[V]	SUB	GATEMAT	GATEIMP	SOIVBB	VT[V]
LOGIC	PMISFET	SOI	SiGe	P	O	-0.3	SOI	SiGe	P	3V	-0.3
	NMISFET	SOI	SiGe	P	O	0.3	SOI	SiGe	P	3V	0.3
	PMISFET	SOI	SiGe	P	O	-0.3	SOI	Poly-Si	N	3V	-1.0
SRAM	NMISFET	SOI	SiGe	P	O	0.3	SOI	Poly-Si	P	3V	0.6

SOISUB		STANDARD						LOWPOWER			
		SUB	GATEMAT	GATEIMP	SOIVBB	VT[V]	SUB	GATEMAT	GATEIMP	SOIVBB	VT[V]
LOGIC	PMISFET	SOI	VERTICALMOS				SOI	Poly-Si	N	X	-0.8
	NMISFET	SOI	Poly-Si	P	3V	0.6	SOI	Poly-Si	P	X	0.8
	PMISFET	SOI	VERTICALMOS				SOI	Poly-Si	N	X	-0.8
SRAM	NMISFET	SOI	Poly-Si	P	3V	0.6	SOI	Poly-Si	P	X	0.8

HYBRIDSUB		HIGHSPEED					STANDARD				
		SUB	GATEMAT	GATEIMP	SOIVBB	VT[V]	SUB	GATEMAT	GATEIMP	SOIVBB	VT[V]
LOGIC	PMISFET	SOI	SiGe	P	O	-0.3	SOI	SiGe	P	3V	-0.3
	NMISFET	SOI	SiGe	P	O	0.3	SOI	SiGe	P	3V	0.3
SRAM	PMISFET	SOI	SiGe	P	O	-0.3	SOI	Poly-Si	N	3V	-1.0
	NMISFET	SOI	SiGe	P	O	0.3	SOI	Poly-Si	P	3V	0.6
IO/Analog/SW		BULK	-	-	-	ANY	BULK	-	-	-	ANY

HYBRIDSUB		STANDARD					LOWPOWER				
		SUB	GATEMAT	GATEIMP	SOIVBB	VT[V]	SUB	GATEMAT	GATEIMP	SOIVBB	VT[V]
LOGIC	PMISFET	BULK	-	-	-	ANY	BULK	-	-	-	ANY
	NMISFET	BULK	-	-	-	ANY	BULK	-	-	-	ANY
SRAM	PMISFET	SOI	VERTICALMOS				SOI	Poly-Si	N	X	-0.8
	NMISFET	SOI	SiGe	P	NONE	0.5	SOI	Poly-Si	P	X	0.8
IO / Analog / SW		BULK	-	-	-	ANY	BULK	-	-	-	ANY

*FIG. 13*

		HIGH SPEED 300MHz~ Vdd<1.0V	STANDARD 100MHz~300MHz Vdd≐1.0V	LOW POWER ~100MHz Vdd>1.0V
Logic	PMOSVT	-0.3V~-0.1V	-0.4V~-0.2V	-0.9V~-0.7V
	NMOSVT	0.1V~0.3V	0.2V~0.4V	0.7V~0.9V
SRAM	PMOSVT	-0.5V~-0.3V	-1.0V~-0.8V	-0.9V~-0.7V
	NMOSVT	0.2V~0.4V	0.4V~0.6V	0.7V~0.9V

*FIG. 14*

GATE MAT	Poly-Si		SiGe	
GATE IMP	P	N	P	N
PMOS Vto	+0.2V	-0.8V	-0.1V	-0.8V
NMOS Vto	+0.8V	-0.2V	0.5V	-0.2V

FIG. 15

	ELE	BULK	FD-SOI
V <sub>bbb</sub>	L <sub>Vth</sub> MOS + V <sub>BBBCRT</sub>	EFFECT IS LOW UNDER 100nm	EFFECT EVEN UNDER 100nm
V <sub>bbf</sub>	H <sub>Vth</sub> MOS + V <sub>BBFCRT</sub>	EFFECT IS LOW AT HIGH TEMPERATURE LEAK CURRENT IS LARGE	HIGH TEMPERATURE OPERATION AVAILABLE, SMALL LEAK CURRENT, ON CURRENT LARGE
V <sub>bbact</sub>	V <sub>th</sub> MOS + M <sub>N</sub> TCRT + V <sub>L</sub> TCRT	WITH ABOVE REASONS, CORRECTIONS FOR V <sub>TH</sub> DISPERSION IS NOT EFFECTIVE	EFFECTIVE UNDER 100nm & HIGH TEMPERATURE

FIG. 16

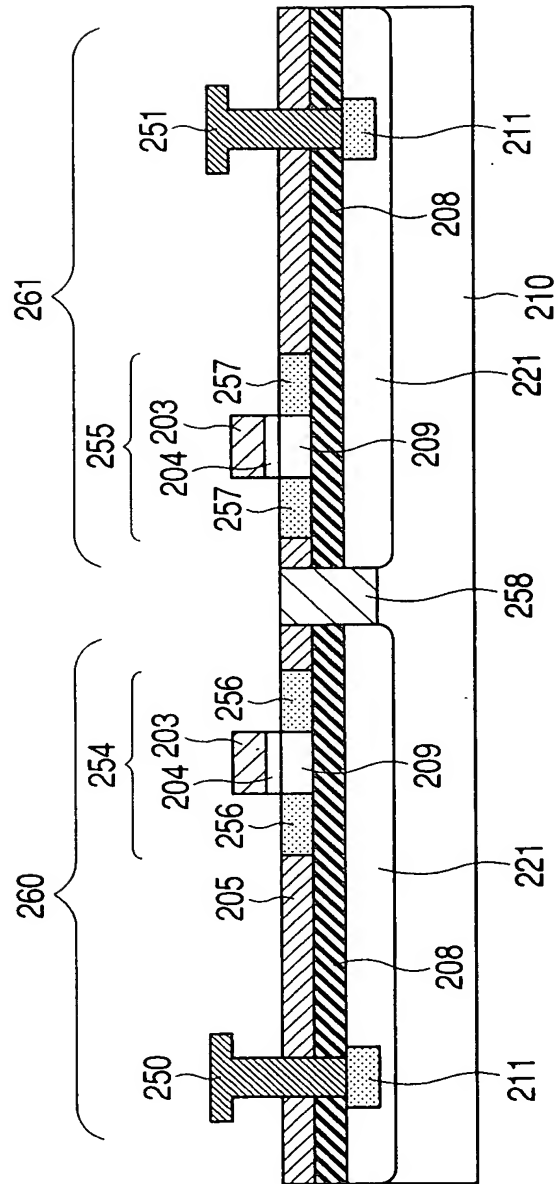


FIG. 17

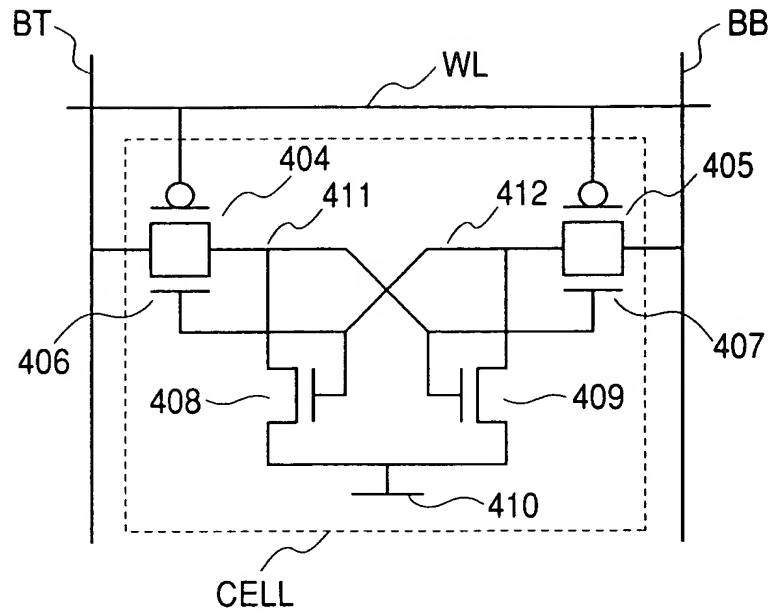
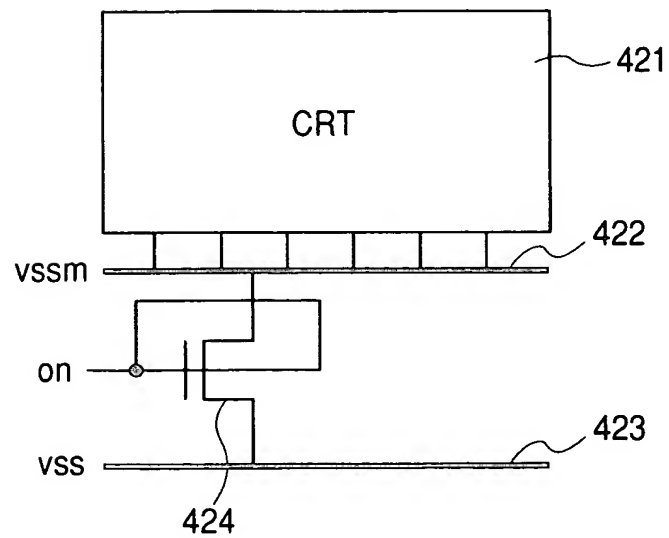


FIG. 18



**FIG. 19**